

ABSTRACT

Lithographic processes utilized for fabrication of micro-machines have been heretofore been plagued by stitching errors and errors arising from the roughness of the surface of the photosensitive material. These errors can be minimized by the utilization of multi-pass exposure techniques to minimize the stitching errors. The surface roughness errors are minimized by a thermal treatment of the surface of the photosensitive material that leaves the bulk of the photosensitive material undisturbed.

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